
Toxics Reduction Plan - Summary

2-Butoxyethanol
CAS: 111-76-2

Prepared for:
Inktech International Corporation
160 Fenmar Drive
Toronto, Ontario
M9L 1M6

Prepared by:
Airzone One Ltd.
222 Matheson Blvd E
Mississauga, ON
L4Z 1X1

1.0 Introduction

1.1. *General Information*

Inktech International Corporation operates a manufacturing facility located at 160 Fenmar Road in Toronto, Ontario (the "Facility"). The facility manufactures UV and conventional screen printing inks.

This toxics reduction plan is for 2-Butoxyethanol (CAS#: 111-76-2). The facility uses 2-Butoxyethanol as a raw material, used in the ink formulation at the facility. The toxic substance is contained in raw materials and released to the atmosphere as part 4 substances (Total VOCs, with further speciation as part 5 substances) through exhaust stacks and/or fugitive emissions.

Table 1 - General Facility Information

NPRI Number	26224
O Reg 127/01 Number	N/A
Number of full time employee equivalents	10
NAICS Code (2 digit)	31-33 - Manufacturing
NAICS Code (4 digit)	3259 - Printing ink manufacturing
NAICS Code (6 digit)	325910 - Printing ink manufacturing
UTM Coordinates	17 T 616647 m E 4846362 m N
Company Legal Name	Inktech International Corporation
Company Trade Name	Inktech International Corporation
Business Number	806675625

1.2. *Plan Contacts*

Public Contact

Mr. Nhan Van Truong,
Technician
Tel: (416) 743-4111
Fax: (416) 743-1511
Email: nhan@inktech-international.com

2.0 Facility's Intent, Objectives and Targets

2.1. *Use*

The act requires that a facility include a statement of intent to reduce the use of the prescribed toxic substance. If the facility does not provide a statement of intent it must provide a reason why it does not intend or why it is not possible to reduce the use of the toxic substance. In addition to this, the facility is required to provide a list of objectives.

Statement of intent:

The Facility does not have a statement of intent.

Reason why the facility does not have a statement of intent: (if applicable)

Inktech is committed to playing a leadership role in protecting the environment. The Facility uses the 2-Butoxyethanol toxic in a few products that are an integral part of the final product formulation, and it is not technically or economically feasible to reduce it. There is no suitable substitute in the product formulations that could provide similar results that are within the customers' demands. Inktech will continue to use this substance in strict accordance with all applicable environmental regulations, and will continue to evaluate opportunities to reduce the use of the toxic substance as an ongoing project.

Objectives: (a list of objectives to reduce if any)

Inktech prides itself on technological innovation in order to produce high quality products in an environmentally responsible manner. They will strive to reduce, eliminate and optimize the use of 2-Butoxyethanol at the facility. No options have been identified, and as part of the continuous improvement practices at the facility, technical advances will be monitored for new opportunities to reduce the use of toxic at the facility.

Quantity Target: (if any)

N/A

Target Timeline: (if any can be expressed in years or described in text box, or no timeline can be selected)

No timeline.

Reason why toxic substance is used at the facility: (from drop down menu options)

For on-site use/ processing.

2.2. *Creation*

The act requires that a facility include a statement of intent to reduce the creation of the prescribed toxic substance. If the facility does not provide a statement of intent it must provide a reason why it does not intend or why it is not possible to reduce the creation of the toxic substance.

Statement of intent:

The Facility does not have a statement of intent.

Reason why the facility does not have a statement of intent:

The Facility does not create the subject substance at the Facility; therefore it is not required to provide a statement of intent on the creation of this substance.

Objectives:

N/A

Quantity Target:

N/A

Target Timeline:

N/A

Reason why toxic substance is created at the facility:

N/A

3.0 Facility's Goals

There are no reasonable substitutions for these substances and many of the reduction options possible have already been implemented in the past.

4.0 Facility TRA Plan (info)

This plan summary is accurate, up to date and reflects the current facility version of the Toxic Reduction Plan.

5.0 Recommendations by TRA Planner

The Planner was constantly consulted during the development of the plan and all recommendations have already been incorporated.

TRA Licence # of TRA Planner who made recommendations and certified the TRA Plan: TSRP0223

6.0 Signed Certification Statements

Certification by highest ranking employee

As of December 19, 2013, I, Christian Bourderon, certify that I have read the toxic substance reduction plan for the toxic substance referred to below and am familiar with its contents, and to my knowledge the plan is factually accurate, with the exception of the regulatory deadline, and the plan complies with the *Toxics Reduction Act, 2009* and Ontario Regulation 455/09 (General) made under that Act.

2-Butoxyethanol

Signed:

A handwritten signature in black ink, appearing to be 'C. Bourderon', written over a horizontal line.

Christian Bourderon

Inktech International Corporation

Certification by toxic substance reduction planner

As of December 19, 2013, I, Franco DiGiovanni, certify that I am familiar with the processes at Inktech International Corporation that use or create the toxic substance referred to below, that I agree with the estimates referred to in subparagraphs 7 iii, iv and v of subsection 4 (1) of the *Toxics Reduction Act, 2009* that are set out in the plan dated December 19, 2013, and, with the exception of the regulatory deadline, that the plan complies with that Act and Ontario Regulation 455/09 (General) made under that Act.

2-Butoxyethanol

Signed:

A handwritten signature in black ink, appearing to read 'FDiG', written in a cursive style.

Franco DiGiovanni

Airzone One Ltd.